

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L20	86	((organic adj acid adj ester) same ((fluidity adj adjuster) (adhesion adj improver) (cissing adj inhibitor) (polymerization adj inhibitor) pigment plasticizer)) and (resist photoresist resin)	USPAT; EPO; JPO; DERWENT	OR	ON	2005/01/19 13:02
L21	13	20 and ("430"/\$.ccls.)	USPAT; EPO; JPO; DERWENT	OR	ON	2005/01/19 13:05
L22	1373	(resin resist photoresist) and ((photoacid acid) near generat\$3) and (photosensitizer sensitizer) and solvent and (\$4acrylate)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/01/19 13:06
L23	655	22 and ("430"/\$.ccls.)	USPAT; EPO; JPO; DERWENT	OR	ON	2005/01/19 13:05
L24	5	(resin resist photoresist) and ((photoacid acid) near generat\$3) and (photosensitizer sensitizer) and solvent and (\$4acrylate same (organic adj acid adj ester))	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/01/19 13:06
L25	170	IMAI-G IMAI-GENICHI IMAI-GENJI	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/01/19 13:09
L26	6	(IMAI-G IMAI-GENICHI IMAI-GENJI) and benzopyran	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/01/19 13:13
L27	6	25 and benzopyran	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/01/19 13:13
L28	23	((((VISIBLE ADJ LIGHT) AND (VISIBLE ADJ LIGHT) AND (resin resist photoresist) AND ((photoacid acid) near generat\$3)) AND (benzopyran (photosensitizer sensitizer))) AND (((VISIBLE ADJ LIGHT) AND (VISIBLE ADJ LIGHT) AND (resin resist photoresist) AND ((photoacid acid) near generat\$3)) AND (benzopyran (photosensitizer sensitizer))) AND (ETHER (ETHER ADJ LINKAGE))) AND (ACRYLATE METHACRYLATE CARBOXYL HYDROXYPHENYL HYDROXYSTYRENE)) AND (IMAI-G IMAI-GENICHI IMAI-GENJI)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/01/19 13:17
S1	2	("20020068237") or ("20020068236").PN.	US-PGPUB; USOCR	OR	OFF	2004/10/05 12:31
S2	1975440	resin resist photoresist	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/10/05 13:09
S3	16077	(photoacid acid) near generat\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/10/05 13:09
S4	78586	photosensitizer sensitizer	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/10/05 13:09
S5	1008314	solvent	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/10/05 13:09
S6	1234	(resin resist photoresist) and ((photoacid acid) near generat\$3) and (photosensitizer sensitizer) and solvent	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/01/19 13:04

S7	5890	benzopyran	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/07/07 12:06
S8	25	((resin resist photoresist) and ((photoacid acid) near generat\$3) and (photosensitizer sensitizer) and solvent) and benzopyran	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/07/07 11:40
S10	6	(IMAI-G IMAI-GENICHI IMAI-GENJI) and benzopyran	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/01/19 13:09
S11	78586	photosensitizer sensitizer	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/07/07 12:06
S12	5890	benzopyran	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/02/24 16:29
S13	61	(photosensitizer sensitizer) same benzopyran	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/02/24 17:30
S14	16077	((photoacid acid) near generat\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/07/07 17:04
S15	1975440	resin resist photoresist	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/02/24 16:29
S16	7	((photosensitizer sensitizer) same benzopyran) and ((photoacid acid) near generat\$3) and (resin resist photoresist)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/07/07 12:07
S17	3	(((photosensitizer sensitizer) same benzopyran) and ((photoacid acid) near generat\$3) and (resin resist photoresist)) not ((IMAI-G IMAI-GENICHI IMAI-GENJI) and benzopyran)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/07/07 12:07
S18	20	((photosensitizer sensitizer) same benzopyran) and (resin resist photoresist)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/07/07 12:08
S19	13	(((photosensitizer sensitizer) same benzopyran) and (resin resist photoresist)) not (((IMAI-G IMAI-GENICHI IMAI-GENJI) and benzopyran) ((photosensitizer sensitizer) same benzopyran) and ((photoacid acid) near generat\$3) and (resin resist photoresist)))	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/10/05 13:09
S20	0	jp-8334897-\$.did.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/07/07 12:10
S21	2	jp-08334897-\$.did.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/07/07 12:26
S22	2	jp-11212252-\$.did. or jp-2000275823 or jp-2000056450	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/07/07 12:27

S23	6	(jp-11212252-\$ did. or jp-2000275823 or jp-2000056450) jp-09138502-\$ did. jp-2000035665-\$ did.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/07/07 12:27
S24	2	jp-2000035665-\$ did.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/07/07 12:49
S25	2	titanocene same (\$5acid near generator)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/07/07 13:47
S26	1	(titanocene adj compound) same (\$5acid near generator)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/07/07 13:47
S27	0	((titanocene adj compound) same (\$5acid near generator)) not (titanocene same (\$5acid near generator))	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/07/07 13:48
S28	51	(radical adj generator) same ((acid photoacid) near generator)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/07/07 14:24
S29	900	(resin resist photoresist binder) and ((photoacid acid) near generator) and (photosensitizer sensitizer)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/07/07 17:03
S30	509	((resin resist photoresist binder) and ((photoacid acid) near generator) and (photosensitizer sensitizer)) and negative	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/07/07 14:26
S31	3797882	photocurable curable cur\$5 negative crosslinkable crosslinked crosslink (cross adj link\$4) cross-link\$4	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/07/07 14:27
S32	509	(((resin resist photoresist binder) and ((photoacid acid) near generator) and (photosensitizer sensitizer)) and negative) and (photocurable curable cur\$5 negative crosslinkable crosslinked crosslink (cross adj link\$4) cross-link\$4)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/07/07 14:28
S33	4167371	dry drying heat-treat\$5 (heat\$5) bak\$4 pre-bake\$4	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/07/07 14:30
S34	4553605	coat coating apply applying applied coated spin-coated spin-coat (spin adj (coated coat coating))	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/07/07 14:31
S35	1655136	irradiate irradiating expose exposure exposing exposed irradiated irradiation	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/07/07 14:31
S36	1640490	develop development developing developed]	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/07/07 14:32
S37	360309	(visible adj light) "VIS"	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/07/07 14:32

S38	57817	((dry drying heat-treat\$5 (heat\$5) bak\$4 pre-bake\$4) and (coat coating apply applying applied coated spin-coated spin-coat (spin adj (coated coat coating))) and (irradiate irradiating expose exposure exposing exposed irradiated irradiation) and (develop development developing developed]) and ((visible adj light) "VIS")	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/07/07 14:33
S39	208	(((resin resist photoresist binder) and ((photoacid acid) near generator) and (photosensitizer sensitizer)) and negative) and ((dry drying heat-treat\$5 (heat\$5) bak\$4 pre-bake\$4) and (coat coating apply applying applied coated spin-coated spin-coat (spin adj (coated coat coating))) and (irradiate irradiating expose exposure exposing exposed irradiated irradiation) and (develop development developing developed]) and ((visible adj light) "VIS")	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/07/07 14:37
S40	50	(((resin resist photoresist binder) and ((photoacid acid) near generator) and (photosensitizer sensitizer)) and negative) and ((dry drying heat-treat\$5 (heat\$5) bak\$4 pre-bake\$4) and (coat coating apply applying applied coated spin-coated spin-coat (spin adj (coated coat coating))) and (irradiate irradiating expose exposure exposing exposed irradiated irradiation) and (develop development developing developed]) and ((visible adj light) "VIS")) and (peel peeling peelable peeled (peel\$4-apart) (peel\$4 near apart))	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/07/07 14:41
S41	27	(((resin resist photoresist binder) and ((photoacid acid) near generator) and (photosensitizer sensitizer)) and negative) and ((dry drying heat-treat\$5 (heat\$5) bak\$4 pre-bake\$4) and (coat coating apply applying applied coated spin-coated spin-coat (spin adj (coated coat coating))) and (irradiate irradiating expose exposure exposing exposed irradiated irradiation) and (develop development developing developed]) and ((visible adj light) "VIS")) and (peel peeling peelable peeled (peel\$4-apart) (peel\$4 near apart))	USPAT; EPO; JPO; DERWENT	OR	ON	2003/07/07 15:48
S42	2	("6033826").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2003/07/07 15:48
S43	1	("6033826").PN.) and (generator) and (\$5sensitizer)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/07/07 16:31
S44	32	pyrene same (benzopyran)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/02/24 17:29
S45	18	((((resin resist photoresist binder) and ((photoacid acid) near generator) and (photosensitizer sensitizer)) and negative) and ((dry drying heat-treat\$5 (heat\$5) bak\$4 pre-bake\$4) and (coat coating apply applying applied coated spin-coated spin-coat (spin adj (coated coat coating))) and (irradiate irradiating expose exposure exposing exposed irradiated irradiation) and (develop development developing developed]) and ((visible adj light) "VIS")) and (peel peeling peelable peeled (peel\$4-apart) (peel\$4 near apart)) and ((visible VIS) near light)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/07/07 17:03
S46	0	((((((resin resist photoresist binder) and ((photoacid acid) near generator) and (photosensitizer sensitizer)) and negative) and ((dry drying heat-treat\$5 (heat\$5) bak\$4 pre-bake\$4) and (coat coating apply applying applied coated spin-coated spin-coat (spin adj (coated coat coating))) and (irradiate irradiating expose exposure exposing exposed irradiated irradiation) and (develop development developing developed]) and ((visible adj light) "VIS")) and (peel peeling peelable peeled (peel\$4-apart) (peel\$4 near apart)) and ((visible VIS) near light)) and benzopyran	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/07/07 17:02

S47	0	(((((resin resist photoresist binder) and ((photoacid acid) near generator) and (photosensitizer sensitizer)) and negative) and ((dry drying heat-treat\$5 (heat\$5 bak\$4 pre-bake\$4) and (coat coating apply applying applied coated spin-coated spin-coat (spin adj (coated coat coating))) and (irradiate irradiating expose exposure exposing exposed irradiated irradiation) and (develop development developing developed])) and ((visible adj light) "VIS"))) and (peel peeling peelable peeled (peel\$4-apart) (peel\$4 near apart))) and benzopyran	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/07/07 17:02
S48	2248	((visible adj light) "VIS") and benzopyran	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/07/07 17:02
S49	395	((((visible adj light) "VIS") and benzopyran) and ((visible VIS) near light)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/07/07 17:03
S50	293	(resin resist photoresist binder) and (((visible adj light) "VIS") and benzopyran) and ((visible VIS) near light))	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/07/07 17:03
S51	21	((photoacid acid) near generat\$3) and ((resin resist photoresist binder) and (((visible adj light) "VIS") and benzopyran) and ((visible VIS) near light)))	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/07/07 17:45
S52	1	ls-148	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/07/07 18:04
S53	2	JP-11258798-\$ DID.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/07/07 18:04
S54	2	benzopyran adj condensed adj ring	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/07/08 11:34
S55	7521	condensed adj ring	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/07/08 11:53
S56	72	proliferating adj agent	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/07/08 13:48
S57	2661	sodium adj lamp	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/07/08 12:09
S58	120	(sodium adj lamp) same (nm wavelength)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/07/08 12:10
S59	72	proliferating adj agent	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/07/08 14:31
S60	2	jp-09138502-\$ did.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/07/08 13:50

S61	2	("6140025").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2003/07/08 14:06
S62	12	(proliferating adj agent) and (resin resist photoresist)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/07/08 14:09
S63	0	(proliferating adj agent) same ((fluidity adj adjuster) (adhesion adj improver) (cissing adj inhibitor) (polymerization adj inhibitor) pigment plasticizer)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/07/08 14:35
S64	134	(organic adj acid adj ester) same ((fluidity adj adjuster) (adhesion adj improver) (cissing adj inhibitor) (polymerization adj inhibitor) pigment plasticizer)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/07/08 14:58
S65	83	((organic adj acid adj ester) same ((fluidity adj adjuster) (adhesion adj improver) (cissing adj inhibitor) (polymerization adj inhibitor) pigment plasticizer)) and (resist photoresist resin)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/07/08 14:58
S66	79	((organic adj acid adj ester) same ((fluidity adj adjuster) (adhesion adj improver) (cissing adj inhibitor) (polymerization adj inhibitor) pigment plasticizer)) and (resist photoresist resin)	USPAT; EPO; JPO; DERWENT	OR	ON	2005/01/19 12:13
S67	2648	(organic adj acid adj ester)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/07/08 14:58
S68	1070	((organic adj acid adj ester)) and (resist photoresist resin)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/07/08 14:59
S69	834	((organic adj acid adj ester)) and (resist photoresist resin)	USPAT	OR	ON	2003/07/08 15:13
S70	0	"430""."270""."1".ccls.	USPAT	OR	ON	2003/07/08 15:00
S71	2718	430/270.1.ccls.	USPAT	OR	ON	2003/07/08 15:09
S72	5	430/270.1.ccls. and (((organic adj acid adj ester)) and (resist photoresist resin))	USPAT	OR	ON	2003/07/08 15:01
S73	6	430/270.1.ccls. and ((organic adj acid adj ester))	USPAT	OR	ON	2003/07/08 15:08
S74	1	(430/270.1.ccls. and ((organic adj acid adj ester))) not (430/270.1.ccls. and (((organic adj acid adj ester)) and (resist photoresist resin)))	USPAT	OR	ON	2003/07/08 15:08
S75	112	"430"/\$.ccls. and ((organic adj acid adj ester))	USPAT	OR	ON	2003/07/08 15:11
S76	5270	"430"/\$.ccls. and (organic adj acid)	USPAT	OR	ON	2003/07/08 15:12
S77	280	430/270.1.ccls. and (organic adj acid)	USPAT	OR	ON	2003/07/08 15:12
S78	269	(430/270.1.ccls. and (organic adj acid)) and (resist photoresist resin)	USPAT	OR	ON	2003/07/08 15:23
S79	89	((430/270.1.ccls. and (organic adj acid)) and (resist photoresist resin)) and (visible near light)	USPAT	OR	ON	2003/07/08 15:30
S80	44	(((430/270.1.ccls. and (organic adj acid)) and (resist photoresist resin)) and (visible near light)) and negative	USPAT	OR	ON	2003/07/08 16:20
S81	97	positive and ((photoacid acid) near generator) and (photosensitizer sensitizer) and (visible near light)	USPAT	OR	ON	2003/07/08 16:21
S82	155	IMAI-G IMAI-GENICHI IMAI-GENJI	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/07/08 16:22
S83	2	(positive and ((photoacid acid) near generator) and (photosensitizer sensitizer) and (visible near light)) and (IMAI-G IMAI-GENICHI IMAI-GENJI)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/02/24 17:30

S84	2	("5801212").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2003/07/08 16:33
S85	2	jp-2000035665-\$.did.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/07/09 08:57
S86	5	((("6492086") or ("6514656") or ("6200731") or ("6156481")).PN.) ((("6072006").PN.)	USPAT	OR	ON	2004/02/24 16:24
S87	43324	VISIBLE ADJ LIGHT	USPAT	OR	ON	2004/02/24 16:29
S88	6442	benzopyran	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/02/24 16:29
S89	77113	VISIBLE ADJ LIGHT	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/02/24 16:29
S90	2089122	resin resist photoresist	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/02/24 16:29
S91	18290	(photoacid acid) near generat\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/02/24 16:30
S92	517	(VISIBLE ADJ LIGHT) AND (VISIBLE ADJ LIGHT) AND (resin resist photoresist) AND ((photoacid acid) near generat\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/02/24 16:30
S93	82793	photosensitizer sensitizer	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/02/24 16:30
S94	88839	benzopyran (photosensitizer sensitizer)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/02/24 16:30
S95	272	((VISIBLE ADJ LIGHT) AND (VISIBLE ADJ LIGHT) AND (resin resist photoresist) AND ((photoacid acid) near generat\$3)) AND (benzopyran (photosensitizer sensitizer))	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/02/24 16:30
S96	462933	ACRYLATE METHACRYLATE CARBOXYL HYDROXYPHENYL HYDROXYSTYRENE	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/02/24 16:31
S97	518060	ETHER	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/02/24 16:31
S98	10822	ETHER ADJ LINKAGE	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/02/24 19:31
S99	248	(((VISIBLE ADJ LIGHT) AND (VISIBLE ADJ LIGHT) AND (resin resist photoresist) AND ((photoacid acid) near generat\$3)) AND (benzopyran (photosensitizer sensitizer))) AND (ETHER (ETHER ADJ LINKAGE))	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/02/24 16:31

S10 0	248	((((VISIBLE ADJ LIGHT) AND (VISIBLE ADJ LIGHT) AND (resin resist photoresist) AND ((photoacid acid) near generat\$3)) AND (benzopyran (photosensitizer sensitizer))) AND (((VISIBLE ADJ LIGHT) AND (VISIBLE ADJ LIGHT) AND (resin resist photoresist) AND ((photoacid acid) near generat\$3)) AND (benzopyran (photosensitizer sensitizer))) AND (ETHER (ETHER ADJ LINKAGE)))	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/02/24 16:32
S10 1	237	((((VISIBLE ADJ LIGHT) AND (VISIBLE ADJ LIGHT) AND (resin resist photoresist) AND ((photoacid acid) near generat\$3)) AND (benzopyran (photosensitizer sensitizer))) AND (((VISIBLE ADJ LIGHT) AND (VISIBLE ADJ LIGHT) AND (resin resist photoresist) AND ((photoacid acid) near generat\$3)) AND (benzopyran (photosensitizer sensitizer))) AND (ETHER (ETHER ADJ LINKAGE)))) AND (ACRYLATE METHACRYLATE CARBOXYL HYDROXYPHENYL HYDROXYSTYRENE)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/02/24 16:32
S10 2	7	((((VISIBLE ADJ LIGHT) AND (VISIBLE ADJ LIGHT) AND (resin resist photoresist) AND ((photoacid acid) near generat\$3)) AND (benzopyran (photosensitizer sensitizer))) AND (((VISIBLE ADJ LIGHT) AND (VISIBLE ADJ LIGHT) AND (resin resist photoresist) AND ((photoacid acid) near generat\$3)) AND (benzopyran (photosensitizer sensitizer))) AND (ETHER (ETHER ADJ LINKAGE)))) AND (ACRYLATE METHACRYLATE CARBOXYL HYDROXYPHENYL HYDROXYSTYRENE)) AND benzopyran	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/10/05 13:10
S10 3	0	((("6492086") or ("6514656") or ("6200731") or ("6156481")). PN.) AND benzopyran	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/02/24 16:45
S10 4	161	IMAI-G IMAI-GENICHI IMAI-GENJI	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/02/24 16:45
S10 5	14	((((VISIBLE ADJ LIGHT) AND (VISIBLE ADJ LIGHT) AND (resin resist photoresist) AND ((photoacid acid) near generat\$3)) AND (benzopyran (photosensitizer sensitizer))) AND (((VISIBLE ADJ LIGHT) AND (VISIBLE ADJ LIGHT) AND (resin resist photoresist) AND ((photoacid acid) near generat\$3)) AND (benzopyran (photosensitizer sensitizer))) AND (ETHER (ETHER ADJ LINKAGE)))) AND (ACRYLATE METHACRYLATE CARBOXYL HYDROXYPHENYL HYDROXYSTYRENE)) AND (IMAI-G IMAI-GENICHI IMAI-GENJI)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/01/19 13:17
S10 6	223	((((VISIBLE ADJ LIGHT) AND (VISIBLE ADJ LIGHT) AND (resin resist photoresist) AND ((photoacid acid) near generat\$3)) AND (benzopyran (photosensitizer sensitizer))) AND (((VISIBLE ADJ LIGHT) AND (VISIBLE ADJ LIGHT) AND (resin resist photoresist) AND ((photoacid acid) near generat\$3)) AND (benzopyran (photosensitizer sensitizer))) AND (ETHER (ETHER ADJ LINKAGE)))) AND (ACRYLATE METHACRYLATE CARBOXYL HYDROXYPHENYL HYDROXYSTYRENE)) not (IMAI-G IMAI-GENICHI IMAI-GENJI)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/02/24 17:03
S10 7	6733	(irradiat\$3 expos\$4) adj4 (visible adj light)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/02/24 19:46
S10 8	47	((((((VISIBLE ADJ LIGHT) AND (VISIBLE ADJ LIGHT) AND (resin resist photoresist) AND ((photoacid acid) near generat\$3)) AND (benzopyran (photosensitizer sensitizer))) AND (((VISIBLE ADJ LIGHT) AND (VISIBLE ADJ LIGHT) AND (resin resist photoresist) AND ((photoacid acid) near generat\$3)) AND (benzopyran (photosensitizer sensitizer))) AND (ETHER (ETHER ADJ LINKAGE)))) AND (ACRYLATE METHACRYLATE CARBOXYL HYDROXYPHENYL HYDROXYSTYRENE)) not (IMAI-G IMAI-GENICHI IMAI-GENJI)) and ((irradiat\$3 expos\$4) adj4 (visible adj light))	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/02/24 17:03
S10 9	36	pyrene same (benzopyran)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/02/24 17:29

S11 0	10	((positive and ((photoacid acid) near generator) and (photosensitizer sensitizer) and (visible near light)) and (IMAI-G IMAI-GENICHI IMAI-GENJI)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/02/24 17:30
S11 1	3	((photosensitizer sensitizer) same benzopyran) and (resin resist photoresist) and ((photoacid acid) near generat\$3) and ((irradiat\$3 expos\$4) adj4 (visible adj light))	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/02/24 17:34
S11 2	0	"20020068236".URPN.	USPAT	OR	ON	2004/02/24 17:32
S11 3	3	((photosensitizer sensitizer) same benzopyran) and ((irradiat\$3 expos\$4) adj4 (visible adj light))	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/02/24 17:34
S11 4	7	((photosensitizer sensitizer) same benzopyran) and (resin resist photoresist) and ((photoacid acid) near generat\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/02/24 17:34
S11 5	4	(((photosensitizer sensitizer) same benzopyran) and (resin resist photoresist) and ((photoacid acid) near generat\$3) not (((photosensitizer sensitizer) same benzopyran) and ((irradiat\$3 expos\$4) adj4 (visible adj light))))	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/02/24 17:34
S11 6	2	(photosensitizer sensitizer) same (benzopyran adj condensed adj ring)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/02/24 17:35
S11 7	67	(photosensitizer sensitizer) same benzopyran	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/02/24 17:36
S11 8	2	("6072006").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2004/02/24 18:33
S11 9	2	photoacid adj proliferating adj agent	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/02/24 18:35
S12 0	2	("6033826").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2004/02/24 18:35
S12 1	9	(("6492086") or ("6514656") or ("6200731") or ("6156481")).PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2004/02/24 19:06
S12 2	2	("6072006").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2004/02/24 19:06
S12 3	2	(photocurable and ((photoacid acid) near generat\$3) and (photosensitizer sensitizer)) and ((photosensitizer sensitizer) same benzopyran)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/02/24 19:31
S12 4	129	photocurable and ((photoacid acid) near generat\$3) and (photosensitizer sensitizer)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/02/24 19:39
S12 5	3	("4548890" "5055439" "5849809").PN.	USPAT	OR	ON	2004/02/24 19:33

S12 6	1	"6140025".URPN.	USPAT	OR	ON	2004/02/24 19:35
S12 7	0	wo-200305126-\$ did.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/02/24 19:39
S12 8	1	wo-2003005126-\$ did.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/02/24 19:40
S12 9	18	(photocurable and ((photoacid acid) near generat\$3) and (photosensitizer sensitizer)) and ((irradiat\$3 expos\$4) adj4 (visible adj light))	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/03/15 15:14
S13 0	4	("5338854" "5446157" "5498641" "5723218").PN.	USPAT	OR	ON	2004/02/24 19:54
S13 1	1	"6106999".URPN.	USPAT	OR	ON	2004/02/24 19:58
S13 2	0	("6140025").PN.	US-PGPUB; USOCR	OR	OFF	2004/03/15 14:08
S13 3	1	("6140025").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2004/03/15 15:37
S13 4	11	(PHOTOCURABLE ADJ RESIN) AND ((PHOTOACID ACID) ADJ GENERATOR) AND (PHOTOSENSITIZER)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/03/15 15:15
S13 5	6478	BENZOPYRAN	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/03/15 15:15
S13 6	2	((PHOTOCURABLE ADJ RESIN) AND ((PHOTOACID ACID) ADJ GENERATOR) AND (PHOTOSENSITIZER)) AND BENZOPYRAN	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/03/15 15:18
S13 7	9	((PHOTOCURABLE ADJ RESIN) AND ((PHOTOACID ACID) ADJ GENERATOR) AND (PHOTOSENSITIZER)) NOT (((PHOTOCURABLE ADJ RESIN) AND ((PHOTOACID ACID) ADJ GENERATOR) AND (PHOTOSENSITIZER)) AND BENZOPYRAN)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/03/15 15:18
S13 8	4	("5338854" "5446157" "5498641" "5723218").PN.	USPAT	OR	ON	2004/03/15 15:21
S13 9	1	"6106999".URPN.	USPAT	OR	ON	2004/03/15 16:50
S14 0	1	("6033826").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2004/03/15 15:46
S14 1	77707	visible adj light	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/03/15 15:46
S14 2	7618	photocurable	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/03/15 15:46
S14 3	1032	(visible adj light) and photocurable	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/03/15 15:46
S14 4	50	((visible adj light) and photocurable) and ((photoacid acid) adj generator)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/03/15 15:47

S14 5	5655	"112" and (photosensitizer sensitizer)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/03/15 15:47
S14 6	43	((visible adj light) and photocurable) and ((photoacid acid) adj generator) and (photosensitizer sensitizer)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/03/15 15:47
S14 7	42	(((visible adj light) and photocurable) and ((photoacid acid) adj generator)) and (photosensitizer sensitizer)) not (((PHOTOCURABLE ADJ RESIN) AND ((PHOTOACID ACID) ADJ GENERATOR) AND (PHOTOSENSITIZER)) AND BENZOPYRAN)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/03/15 15:47
S14 8	40	(((visible adj light) and photocurable) and ((photoacid acid) adj generator)) and (photosensitizer sensitizer)) not (((PHOTOCURABLE ADJ RESIN) AND ((PHOTOACID ACID) ADJ GENERATOR) AND (PHOTOSENSITIZER)) AND BENZOPYRAN)) and (resin)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/10/05 13:10
S14 9	4	("6555286").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2004/03/15 15:59
S15 0	7	("6106999").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2004/03/15 16:50
S15 1	2	("6033826") or ("6072006").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2004/10/05 13:08
S15 2	152068	aqueous near10 composition	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/10/05 13:09
S15 3	2199247	resin resist photoresist	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/10/05 13:09
S15 4	20418	(photoacid acid) near generat\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/10/05 13:09
S15 5	87183	photosensitizer sensitizer	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/10/05 13:09
S15 6	1118321	solvent	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/10/05 13:09
S15 7	166	IMAI-G IMAI-GENICHI IMAI-GENJI	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/10/05 13:09
S15 8	15	((photosensitizer sensitizer) same benzopyran) and (resin resist photoresist)) not (((IMAI-G IMAI-GENICHI IMAI-GENJI) and benzopyran) ((photosensitizer sensitizer) same benzopyran) and ((photoacid acid) near generat\$3) and (resin resist photoresist)))	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/10/05 13:09

S15 9	32	((((VISIBLE ADJ LIGHT) AND (VISIBLE ADJ LIGHT) AND (resin resist photoresist) AND ((photoacid acid) near generat\$3)) AND (benzopyran (photosensitizer sensitizer))) AND (((VISIBLE ADJ LIGHT) AND (VISIBLE ADJ LIGHT) AND (resin resist photoresist) AND ((photoacid acid) near generat\$3)) AND (benzopyran (photosensitizer sensitizer))) AND (ETHER (ETHER ADJ LINKAGE)))) AND (ACRYLATE METHACRYLATE CARBOXYL HYDROXYPHENYL HYDROXYSTYRENE)) AND benzopyran	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/10/05 13:10
S16 0	51	((((visible adj light) and photocurable) and ((photoacid acid) adj generator)) and (photosensitizer sensitizer)) not (((PHOTOCURABLE ADJ RESIN) AND ((PHOTOACID ACID) ADJ GENERATOR) AND (PHOTOSENSITIZER)) AND BENZOPYRAN)) and (resin)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/10/05 13:10
S16 1	31	(S159 S160 S158) and S152	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/10/05 13:11
S16 2	554	S152 and S153 and S154 and S155 and S156	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/10/05 13:12
S16 3	27	S157 and S152	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/10/05 13:11
S16 4	54	S161 S163	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/10/05 15:54
S16 5	2	("5496678").PN.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2004/10/05 15:54